

JCWSCS 16 JUL 2004

PAGE 1/3 \* RCVD AT 7/15/2004 9:09:56 PM [Eastern Daylight Time] \* SVR:USPTO-EFAXRF-20 \* DNS:7469195 \* CSID:4153712201 \* DURATION (mm-ss):01-18

ATTORNEY DOCKET NO.: TSMC2003-1412(N1280-280)  
AS CORRECTED

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: **Chao-Hsiung Wang et al.**

Serial No.: **10/824,750**

Examiner: Not Known Yet

Filed: **April 15, 2004**

Group Art Unit: 1752

Confirmation No. 7047

For: **METHOD AND SYSTEM FOR IMMERSION LITHOGRAPHY USING HIGH PH IMMERSION FLUID**

**REQUEST FOR CORRECTED FILING RECEIPT**

Sir:

Attached is a copy of the official Filing Receipt received from the PTO in the above application for which issuance of a corrected filing receipt is respectfully requested. Please correct the title as indicated below.

**Attorney Docket No. should be TSMC2003-1412(N1280-00280)**

A copy of the Filing Receipt is also attached with the foregoing correction to the title indicated on the official Filing Receipt.

Respectfully submitted,

Date:

July 15, 2004



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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/824,750	04/15/2004	1752	1004	N1280-002480 TSMC2003-4836-1412	2	33	3

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DUANE MORRIS

CONFIRMATION NO. 7047

FILING RECEIPT



\*OC000000013083296\*

Date Mailed: 06/28/2004

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections, facsimile number 703-746-5195. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

**Applicant(s)**

Chao -Hsiung Wang, Residence Not Provided;  
 Hornq-Huei Tseng, Residence Not Provided;

**Assignment For Published Patent Application**

Taiwan Semiconductor Manufacturing Company, Ltd.;

**Domestic Priority data as claimed by applicant**

**Foreign Applications**

**If Required, Foreign Filing License Granted: 06/26/2004**

**Projected Publication Date: To Be Determined - pending completion of Missing Parts**

**Non-Publication Request: No**

**Early Publication Request: No**

**Title**

Method and system for immersion lithography using high PH immersion fluid



**Preliminary Class**

430

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Title 37, Code of Federal Regulations, 5.11 & 5.15**

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